

## 2D Materials

Room 208 W - Session 2D+EM+NS+QS+SS+TF-WeA

### 2D Materials: Synthesis and Processing

**Moderators:** Peter Sutter, University of Nebraska, Tiancong Zhu, Purdue University

2:15pm **2D+EM+NS+QS+SS+TF-WeA-1 Process Discovery for Quantum Materials, Stephan Hofmann**, University of Cambridge, UK **INVITED**

Effective heterogeneous integration of low-dimensional nanomaterials in applications ranging from quantum electronics to biomedical devices requires a detailed understanding of different formation and interfacing reactions and the ability to synergize these processes. Process development largely still follows an Edisonian trial-and-error approach, blind and constrained by conventional reactors. This is not only wasteful and frustratingly slow, but hinders scientific breakthroughs in crystal growth and innovation in new deposition technology. This talk will focus on our cross-correlative, high-throughput operando approaches and combinatorial close-space sublimation (CSS) based process design to accelerate process discovery. We show operando spectroscopic imaging ellipsometry and scanning electron microscopy with machine-learning assisted analysis and parameter space exploration for salt-assisted WS<sub>2</sub> layer CVD and TMD oxidation phenomena, and how direct kinetic process data can open data driven approaches to advance the required understanding of underpinning mechanisms.[1] We show that CSS is a highly promising alternative to conventional powder-furnace chemical vapour deposition, offering superior efficiency, precise structural control, scalability, and adaptable process designs. As part of processability and stability assessment, we also explore oxidation kinetics of TMD materials, [2] aided by atomistic modelling using machine-learned force fields.[3]

[1] Yang et al., Chem. Mat. 37, 989 (2025)

[2] Sahota et al., ACS Appl. Nano Mat., asap (2025)

[3] Gsanyi et al., arXiv:2401.00096, 2023

2:45pm **2D+EM+NS+QS+SS+TF-WeA-3 Selective Area Epitaxy of van der Waals Materials, Ryan Trice**, Stephanie Law, Penn State University

Two-dimensional (2D) van der Waals (vdW) materials are interesting for a variety of applications, ranging from optoelectronics and photocatalysis to energy storage and topological devices. However, vdW materials synthesized using common techniques like chemical or physical vapor deposition often have a high density of growth-related defects, including grain boundaries, twin defects, pyramidal growth, and spiral defects. While pyramidal growth can be minimized through higher growth temperatures, grain boundaries, twin defects, and spiral defects are much harder to overcome. For many applications, especially in electronics and optics, these defects lead to non-radiative recombination, electron scattering, and other undesirable effects. Furthermore, the fabrication of 2D materials into quantum dots (QDs) through bottom-up methods faces problems with precise location placement and polydispersity in the QDs' diameters. This makes the QDs difficult to characterize and is not ideal for most quantum computing and optical setups. Top-down nanofabrication approaches fix this issue but often cause significant damage to the surfaces or edges of the materials. To address these issues, we used molecular beam epitaxy (MBE) combined with selective area epitaxy (SAE) to grow Bi<sub>2</sub>Se<sub>3</sub> thin films. SAE is a technique in which thin films nucleate and grow in defined areas on a wafer. This is done using a patterned mask where growth conditions are selected such that the film will only nucleate on the substrate.

In this talk, we will describe SAE growth of Bi<sub>2</sub>Se<sub>3</sub> on Al<sub>2</sub>O<sub>3</sub> (0001) and Si (111) substrates using an atomic layer deposition SiO<sub>2</sub> mask. Etching of the SiO<sub>2</sub> mask was done with a wet chemical etch, resulting in micron-scale holes of various shapes and sizes. The processed substrates were then loaded into an MBE chamber for the growth of the Bi<sub>2</sub>Se<sub>3</sub> film. First, we will discuss the effects of different substrate temperatures on the selective growth of the Bi<sub>2</sub>Se<sub>3</sub> thin films. Second, we will discuss the geometric influence of various shaped patterns on the crystal quality of the selectively grown films. Third, we will look at the effect and viability of nano-scale patterns for selective growth of vdW materials. Further studies will focus on using different materials for the substrate and mask. This approach could allow us to grow wafer-scale, defect-free 2D vdW QDs at specified areas on the wafer, thereby increasing the scalability and applicability of these materials to real-world challenges.

3:00pm **2D+EM+NS+QS+SS+TF-WeA-4 Precision Synthesis and Conversion of 2D Materials by Pulsed Laser Deposition with in Situ Diagnostics, Daniel T. Yimam**, Sumner B. Harris, Oak Ridge National Laboratory, USA; Austin Houston, University of Tennessee Knoxville; Ivan Vlassiouk, Oak Ridge National Laboratory, USA; Alexander Puzetzy, Oak Ridge National Laboratory; Gerd Duscher, University of Tennessee Knoxville; Kai Xiao, Oak Ridge National Laboratory, USA; David B. Geohegan, University of Tennessee Knoxville

Over the past few decades, 2D monolayers and heterostructures have become central to nanoscience, offering promising applications in electronics, sensing, and future computing. In addition to their exciting functional properties, significant progress has been made in their bottom-up synthesis and subsequent processing. Techniques such as encapsulation, doping, and implantation in atomically thin 2D materials are crucial to transitioning them from fundamental research to scalable, real-world applications, while enabling the emergence of novel properties. However, the ultrathin nature that makes 2D materials attractive also poses substantial challenges for traditional plasma-based processing methods. To fully harness the potential, it is essential to develop reliable processing techniques that offer precise control and reproducibility.

Pulsed laser deposition (PLD) is a promising non-equilibrium method that allows precise control over the kinetic energy (KE) of ablated species. In this work, we investigate plasma plume interactions with 2D materials using *in situ* plasma diagnostics and optical characterization tools. We demonstrate that a deep understanding and control of plasma plume dynamics enables new approaches for 2D material engineering, including the formation of Janus monolayers, metal atom implantation, and encapsulation with minimal damage. Our approach allows for low temperature substitution and implantation of foreign atoms, such as chalcogens and metals, facilitating the selective synthesis of Janus monolayers and alloys. These findings highlight the potential of PLD to drive the practical advancements in 2D materials for microelectronics and quantum information science.

This work was supported by the U.S. DOE, Office of Science, Materials Sciences and Engineering Division and the Center for Nanophase Materials Sciences, which is a DOE Office of Science User Facility.

**Keywords:** Pulsed laser deposition, chalcogenide substitution, 2D materials, implantation, in situ diagnostics.

3:15pm **2D+EM+NS+QS+SS+TF-WeA-5 AVS Peter Mark Memorial Award Talk: Exploiting Thin Film Phase Diagrams for Synthesizing 2D Transition Metal Dichalcogenides, Nicholas R. Glavin**, Air Force Research Laboratory **INVITED**

Synthesis of 2D transition metal dichalcogenides for specific applications in electronics, optoelectronic, and advanced coatings remains a critical bottleneck for many industrial applications. In this talk, we will highlight leveraging thin film phase diagrams to rapidly explore the vast parameter space in synthesizing these novel materials. This technique uses laser processing to locally modify regions within the film and coupled with high throughput characterization, rapidly assesses material state and quality for next generation sensors, optical coatings, and low power electronics.

4:15pm **2D+EM+NS+QS+SS+TF-WeA-9 Designer van der Waals Materials for Quantum Optical Emission, Shengxi Huang**, Rice University **INVITED**

Designer van der Waals (vdW) materials offers enormous opportunities to tune material properties for various applications. Isolated, optically-active defects generated in vdW materials could lead to single photon emission. 2D vdW materials as host materials for single photon emission hold various advantages, such as high optical extraction efficiency from the atomically-thin layered materials, and readiness to integrate with on-chip photonic and electronic devices. However, single photon emission from 2D vdW materials typically suffers from low purity and lack of controllability, due to the sensitivity of these atomically-thin materials to external dielectric environments, surface defects and adsorbents, and strains and wrinkles introduced during material processing. This talk introduces our recent efforts to improve the single photon purity and controllability in vdW materials. We developed novel defect structures that can overcome several current issues, and explored their electronic structure and tunability in optical emission. Through a combination of approaches, including strain engineering, heterostacking, employing optical selection rules for excitation and detection, optimization of material synthesis and handling, we were able to achieve high purity (> 98%) for single photons emitted from 2D transition metal dichalcogenides (TMDs) at cryogenic temperature and in hBN at room temperature. This work provides deep insights into the electronic, spin, and valley properties of TMDs and hBN. It also paves the

way towards the application of 2D vdW materials for quantum optical applications. The materials engineering approaches developed here can be applied to the optimization of other optical and quantum materials.

4:45pm **2D+EM+NS+QS+SS+TF-WeA-11 Macroscopic Tin Monochalcogenide Van Der Waals Ferroics: Growth, Domain Structures, Curie Temperatures and Lateral Heterostructures, Eli Sutter, Peter Sutter, University of Nebraska - Lincoln**

2D and layered van der Waals crystals present opportunities for creating new families of ferroics with switchable electric polarization, elastic strain, or magnetic order at thicknesses down to the single-layer limit. Synthesis, however, typically leads to small crystals with sizes ranging from below 100 nm (e.g., for SnTe ferroelectrics) to a few  $\mu\text{m}$  (e.g., for SnSe ferroelectrics). The limited size and proximity to edges affects the ferroelectric and ferroelastic domain patterns, restricts the experimental methods available to probe emerging properties, and severely limits the ability to fabricate complex device architectures required for accessing functionalities in van der Waals ferroelectrics.

Here, we report the realization of in-plane ferroelectric few-layer crystals of the monochalcogenides tin(II) sulfide and selenide (SnS, SnSe) whose linear dimensions exceed the current state of the art by up to one order of magnitude. Such large crystals allow the investigation of ferroic domain patterns that are unaffected by edges and finite size effects. Analysis of the abundant stripe domains by electron microscopy and nanobeam electron diffraction shows two distinct domain types, twin domains separated by positively charged walls with alternating head-to-head and tail-to-tail polarization as well as not previously observed purely rotational domains connected by neutral domain walls with head-to-tail dipoles. Access to large ultrathin crystals allowed determining the Curie temperatures of few-layer SnSe<sup>1</sup> and SnS van der Waals ferroelectrics.

Finally, we demonstrate the integration of the ultrathin ferroelectric SnSe and SnS into lateral heterostructures.<sup>2</sup> A two-step process produces crystals comprising an SnSe core laterally joined to an SnS edge-band, as confirmed by Raman spectroscopy, electron microscopy imaging, and diffraction. The ability of the lateral interface to direct excited carriers, probed by cathodoluminescence, shows electron transfer over 560 nm diffusion length from the SnS edge-band. The ferroelectric heterostructures adopt two domain configurations, with domains either constrained to the SnSe core or propagating across the entire SnSe-SnS flakes.

The combined results demonstrate industrial scale in-plane ferroelectrics as well as multifunctional van der Waals heterostructures, presenting extraordinary opportunities for manipulating ferroelectric domain patterns and carrier flow.

(1) Sutter, E.; Ghimire, P.; Sutter, P. *J Am Chem Soc* **2024**, *146* (46), 31961-31968. DOI: 10.1021/jacs.4c11558.

(2) Sutter, E.; Ghimire, P.; Sutter, P. *ACS Nano* **2024**, *18* (44), 30829-30837. DOI: 10.1021/acsnano.4c11341.

5:00pm **2D+EM+NS+QS+SS+TF-WeA-12 Machine Learning Analysis of Molecular Beam Epitaxy Growth Conditions, Mingyu Yu, Ryan Trice, Isaiah Moses, Wesley Reinhart, Stephanie Law, Penn State University**

Machine learning models hold the potential to explore parameter space autonomously, quickly establish process-performance relationships, and diagnose material synthesis in real time. This reduces reliance on manual intervention in parameter space exploration, enabling more precise and efficient mechanistic control. For molecular beam epitaxy (MBE), despite its breakthroughs in materials synthesis, its stringent growth conditions and complex epitaxial mechanisms make the process of optimizing growth process time-consuming and expensive. Therefore, leveraging machine learning to develop autonomous MBE growth platforms presents a highly promising prospect. Our study on the multi-modal machine learning-guided MBE synthesis is based on a comprehensive high-quality dataset of GaSe thin films grown on GaAs (111)B substrates. GaSe is an emerging two-dimensional semiconductor material with intriguing properties, including thickness-tunable bandgaps, nonlinear optical behaviors, and intrinsic p-type conductivity. Moreover, as a representative member of the van der Waals (vdW) chalcogenide semiconductor family, insights gained from studying GaSe can be extended to other vdW chalcogenides. In this work, we aim to leverage machine learning to analyze the relationships between growth conditions (Ga flux, Se:Ga flux ratio, and substrate temperature) and the resulting sample quality, as well as the correlations among various characterization results including in situ RHEED patterns and ex situ x-ray

diffraction rocking curve full-width at half maximum (FWHM) and atomic force microscopy (AFM) root mean square (RMS) roughness. Unsupervised learning on RHEED patterns reveals a well-defined boundary between high- and low-quality samples, capturing physically meaningful features. Mutual information analysis shows a strong correlation between RHEED embeddings and rocking curve FWHM, while the correlation with AFM RMS roughness is weak. Among key growth conditions, growth rate most strongly influences FWHM, whereas the Se:Ga flux ratio primarily affects RMS roughness and the RHEED embeddings. Supervised learning models trained to predict FWHM and RMS roughness demonstrate moderate accuracy, with significant improvement achieved by incorporating RHEED embeddings. Furthermore, anomaly detection via residual analysis in supervised learning aligns well with unsupervised classification from RHEED, reinforcing the reliability of the predictive models. This study establishes a data-driven framework for machine learning-assisted MBE, paving the way for real-time process control and accelerated optimization of thin-film synthesis.

5:15pm **2D+EM+NS+QS+SS+TF-WeA-13 Promoting Crystallographic Alignment in SnSe Thin Films using Step Edges on MgO by MBE, Jonathan Chin, Marshall Frye, Joshua Wahl, Kayla Chuong, Georgia Institute of Technology; Mengyi Wang, Derrick Liu, Pennsylvania State University; Mingyu Yu, University of Delaware; Qihua Zhang, Nadire Nayir, Adri van Duin, Maria Hilse, Stephanie Law, Pennsylvania State University; Lauren Garten, Georgia Institute of Technology**

SnSe is a van der Waals material that can be scaled down to two dimensions,<sup>1</sup> making it a promising candidate for nanoelectronics such as field effect transistors (FETs).<sup>2</sup> SnSe in the orthorhombic *Pnma* structure exhibits significant electrical anisotropy where the carrier mobility is 45% higher along the [010] direction than the [001] direction in plane,<sup>3</sup> making it necessary to control the in-plane alignment of 2D films for integration into electronic devices. SnSe has been shown to form planar coverage on (100) MgO,<sup>4</sup> with which it has a 1.4% and 5.5% lattice mismatch along the [010] and [001] directions, respectively. However, despite the distinct axial lattice matches, in-situ reflective high-energy electron diffraction (RHEED) shows no preferential SnSe film alignment for films deposited on uncleaved MgO. Therefore, to promote orientation control, we cleaved and annealed the MgO substrates to produce step edges along the surface to increase the local surface energy, thereby encouraging atomic adsorption and alignment. SnSe thin films were then deposited from individual Sn and Se effusion cells via molecular beam epitaxy (MBE) onto the prepared MgO substrates heated to 280 °C for 1-5 minutes with a 1.35:1.00 Se:Sn flux ratio at a 0.083 Å/s growth rate to track the nucleation and growth of SnSe grains. The phase of the SnSe films was confirmed by Raman spectroscopy, exhibiting the characteristic A<sub>g</sub><sup>2</sup>, B<sub>g</sub>, A<sub>g</sub><sup>3</sup>, and A<sub>g</sub><sup>4</sup> phonon modes.<sup>5</sup> In-situ RHEED confirmed the in-plane alignment along the [010] and [001] by RHEED relative to the [100] substrate, matching theory projections made using reactive force field (ReaxFF) simulations. Additionally, atomic force microscopy (AFM) shows SnSe grains nucleating at step edges on MgO, while scanning transmission electron microscopy (STEM) reveals how the aligned SnSe grains propagate laterally off step edges, maintaining crystallographic alignment throughout the film layer. Overall, our results demonstrate that SnSe grains preferentially nucleate along the step edges produced parallel to the [100] edge of the MgO substrates. The alignment of a 2D vdW film facilitated by step edge formation demonstrates how to achieve orientated depositions of similar anisotropic vdW films on a substrate of choice, ultimately facilitating the manufacture of 2D nanoscale electronic devices.

1. Zhang, L.-C. *et al. Sci. Rep.* **6**, 19830 (2016).

2. Chhowalla, M. *et al. Nat. Rev. Mater.* **1**, 1–15 (2016).

3. Zhou, M. *et al. J. Mater. Chem.* **5**, 1247–1254 (2017).

4. Chin, J. R. *et al. Nanoscale* **15**, 9973–9984 (2023).

5. Wu, P. *et al. New J. Phys.* **22**, 083083 (2020).

5:30pm **2D+EM+NS+QS+SS+TF-WeA-14 Synthesis of Millimeter-Scale Single-Crystal  $\alpha$ -MoO<sub>3</sub> Nanosheets on Sapphire, Ryan Spangler, Pennsylvania State University; Thiago Arnaud, Joshua Caldwell, Vanderbilt University; Jon-Paul Maria, Pennsylvania State University**

$\alpha$ -MoO<sub>3</sub> is a van der Waals layered semiconductor with biaxial anisotropy that has recently gained interest as an emerging 2D material with a wide band gap (~3 eV), large work function, and high permittivity. Additionally,  $\alpha$ -MoO<sub>3</sub> exhibits extreme anisotropy of the dielectric function, enabling in-plane and out-of-plane elliptic or even hyperbolic behavior at various wavelengths. Therefore,  $\alpha$ -MoO<sub>3</sub> also possesses great potential for

nanophotonics through the low-loss and directional propagation of hyperbolic phonon polaritons, which result from the interaction of light with lattice vibrations in highly anisotropic polar materials. However, the lack of single-crystal thin film growth techniques limits further advancement of  $\alpha$ -MoO<sub>3</sub>. In this work, we describe a process for the growth of ultra-large, thin, and atomically smooth single crystals of  $\alpha$ -MoO<sub>3</sub> directly on *a*-plane sapphire using an alkali-assisted physical vapor transport method. Important parameters necessary for high-quality growth to be discussed include substrate selection, alkali-to-MoO<sub>3</sub> ratio, and substrate temperature. The growth proceeds through a vapor-liquid-solid (VLS) mechanism enabled by the formation and liquefaction of low-melting point alkali molybdate phases. This growth mode greatly enhances lateral expansion to several millimeters and thicknesses ranging from hundreds of nm down to <5 nm. This is far thinner and more expansive than crystals grown without alkali metal additives, which can exceed several micrometers in thickness while being limited to a few tens of micrometers in lateral dimensions. The thin alkali-assisted sheets exhibit clean step-flow growth without grain boundaries over mm-scale areas as revealed by atomic force microscopy and polarized optical microscopy. Raman spectroscopy and X-ray diffraction indicate the high crystalline quality of the  $\alpha$ -MoO<sub>3</sub> films rivaling that of accessible bulk crystals. We will also investigate the propagation of hyperbolic phonon polaritons using scanning near-field optical microscopy (SNOM) to compare hyperbolic phonon polariton lifetimes to values obtained from exfoliated bulk crystals. We find that this growth technique is suitable for exfoliation-free large-scale single-crystal  $\alpha$ -MoO<sub>3</sub> for nanophotonics and other applications.

5:45pm **2D+EM+NS+QS+SS+TF-WeA-15 Studying the Impacts of Growth Temperature and Seeding Promoters on the Structural and Optoelectronic Properties of ReS<sub>2</sub> Grown by CVD**, *Elycia Wright, Kedar Johnson, Amari Gayle, Robin Rousseau, M.K. Indika Senevirathna, Michael D. Williams, Clark Atlanta University*

Rhenium disulfide (ReS<sub>2</sub>) is a fascinating member of the transition metal dichalcogenide (TMD) family, which has recently gained significant attention due to its distinct distorted octahedral 1T crystal structure characterized by triclinic symmetry. This distinctive structure shows that ReS<sub>2</sub> holds remarkable properties, including anisotropic electronic, optical, and mechanical characteristics. Unlike other TMDs such as MoS<sub>2</sub>, MoSe<sub>2</sub>, WS<sub>2</sub>, and WSe<sub>2</sub>, ReS<sub>2</sub> possesses a band structure that remains consistent regardless of the layer thickness. Due to weak interlayer coupling, it maintains a direct band gap in its bulk and monolayer forms. This unique characteristic makes ReS<sub>2</sub> particularly promising for applications in highly responsive photodetectors. To maximize the potential of ReS<sub>2</sub> for optoelectronic applications, it is essential to address the challenges associated with its anisotropic growth, distorted structure, and weak interlayer interactions. The anisotropic nature of ReS<sub>2</sub> can lead to variations in growth rates in different directions, resulting in multidomain structures that complicate the production of single-crystal ReS<sub>2</sub> on a large scale.

In this study, we will synthesize ReS<sub>2</sub> by chemical vapor deposition (CVD) at various temperatures and utilize seeding promoters to facilitate the growth of single crystals with continuous layers. We will employ advanced techniques such as confocal microscopy, Raman spectroscopy, and photoluminescence spectroscopy to systematically investigate how the growth temperature and seeding promoters affect the structural and optoelectronic properties of ReS<sub>2</sub>.

6:00pm **2D+EM+NS+QS+SS+TF-WeA-16 Growth and Characterization of InSe Thin Films on GaAs(111)B and Si(111)**, *Maria Hilse, Penn State University*

Urgent societal and environmental needs have sparked searches for high-mobility 2D materials with sizeable bandgap and decent stability under ambient conditions for use in ultra-low power, ultra-high performance field effect transistors. With a carrier mobility exceeding 1000 cm<sup>2</sup>/Vs, small electron effective mass, flat electronic band dispersions, excellent optoelectronic, possible ferroelectric properties and a close-to-ideal solar spectrum matched bulk bandgap of 1.26 eV, InSe shows high potential for future use in electronics. Due to the layered nature, and the many members of different polytypes in the InSe materials family, intriguing confinement phenomena and exotic electron-hole coupling mechanisms tunable by the number of single layers add to the potential wealth of properties in InSe.

In this study, InSe thin films were grown by MBE on GaAs(111)B and Si(111). The presence of many InSe phases required a systematic mapping of the growth parameters to identify conditions for single-phase, single-polytype, and single-crystal growth. Through structural characterization in-

and ex-situ using reflection high-energy electron and X-ray diffraction, growth conditions for solely gamma-phase, crystalline InSe films were found. Although the structural properties of the films presented nearly unchanged over a small window of growth conditions, the film morphology was seen to sensitively depend on the Se:In flux ratio. Raman spectroscopy confirmed the phase and polytype assignment deduced from large-area structural characterization.

Microstructure analysis, however, revealed a high degree of structural defects in the films. Nano-scale domains of varying single layer stacking sequences, high-angle rotational domains as well as single layers of unusual bonding configuration resulting in a novel InSe polymorph were found in the films. The total number of defects and the general locations of the new polymorph varied in films across GaAs and Si. The highest structural homogeneity was found for InSe films grown on Si.

Density functional theory calculations for a representative selection of the experimentally observed defects confirmed that most defects, including the novel polymorph have formation energies at or below the thermal budget of the MBE synthesis process. Although the bandgaps of all InSe polytypes and polymorphs possess comparable values, large differences were found in their relative offsets. Due to the random distribution of polytypes and polymorphs in the film, our study suggests a high degree of electronic disorder in these films. Electrical transport showed a variable-range hopping-like behavior supporting the hypothesis of electronic disorder.

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